

Amendments to the Specification

Please amend the specification as follows.

Please amend the paragraph beginning at page 4, line 22, as follows:

A fifth aspect of the invention provides a substrate cleaning apparatus in accordance with any of the first to the third aspects, in which the cleaning roller is rotatably supported on the free end of a swingable swing arm, wherein the swing arm is biased in the direction of bringing the cleaning member into contact with the end face and/or the bevel face of the substrate. This may also allow the end face and/or the bevel face of a flat oriented portion of a substrate having the flat oriented portion to be cleaned by applying to the swing arm an appropriate bias force corresponding to the speed of revolution of the substrate.

Please amend the paragraph beginning at page 5, line 6, as follows:

A sixth aspect of the invention provides a substrate cleaning apparatus according to any of the first to the fifth aspects, in which the apparatus further comprises a contact-location adjusting mechanism for adjusting the contact-location of the cleaning member with the substrate in the vertical direction of the cleaning member. This may allow the cleaning member to be efficiently utilized over the full width in the vertical direction thereof by shifting the cleaning member in the height direction by an appropriate distance according to the amount of abrasion, thus using the cleaning member in an economical manner.